

DERWENT-ACC-NO: 2003-655221

DERWENT-WEEK: 200514

COPYRIGHT 2005 DERWENT INFORMATION LTD

TITLE: Cvd apparatus using plasma

INVENTOR: PARK, Y S

PATENT-ASSIGNEE: KOKUSAI ELECTRIC KOREA[KOKZ] , KOOKJE ELECTRIC KOREA CO  
LTD [KOOKN]

PRIORITY-DATA: 2001KR-0070914 (November 15, 2001)

PATENT-FAMILY:

| PUB-NO          | PUB-DATE         | LANGUAGE | PAGES |
|-----------------|------------------|----------|-------|
| MAIN-IPC        |                  |          |       |
| KR 450286 B     | October 15, 2004 | N/A      | 000   |
| H01L 021/205    |                  |          |       |
| KR 2003040581 A | May 23, 2003     | N/A      | 001   |
| H01L 021/205    |                  |          |       |

APPLICATION-DATA:

| PUB-NO            | APPL-DESCRIPTOR | APPL-NO        | APPL-DATE |
|-------------------|-----------------|----------------|-----------|
| KR 450286B        | N/A             | 2001KR-0070914 |           |
| November 15, 2001 |                 |                |           |
| KR 450286B        | Previous Publ.  | KR2003040581   | N/A       |
| KR2003040581A     | N/A             | 2001KR-0070914 |           |
| November 15, 2001 |                 |                |           |

INT-CL (IPC): H01L021/205

ABSTRACTED-PUB-NO: KR2003040581A

BASIC-ABSTRACT:

NOVELTY - A CVD(Chemical Vapor Deposition) apparatus using plasma is provided to reduce a deposition time and improve the uniformity of a surface of a wafer by installing a plasma generator in the inside of a process chamber.

DETAILED DESCRIPTION - A boat(300) is installed within a process chamber(200).

A plurality of wafers are loaded into the boat. A shower head(400) is used for injecting a process gas to the wafers loaded into the boat. A plasma generator(500) is installed within the shower head in order to form the process gas injected from the shower head to a state of plasma. The shower head is

installed in the inside of the process chamber. A gas induction space is formed by the shower head and a sidewall of the process chamber. A gas induction portion(600) supplies the process gas into the gas induction space of the shower head.

CHOSEN-DRAWING: Dwg.1/10

TITLE-TERMS: CVD APPARATUS PLASMA

DERWENT-CLASS: U11 V05

EPI-CODES: U11-C09B; U11-C09C; V05-F04E; V05-F05C; V05-F05E3; V05-F08D1;

100

